

United States Patent and Trademark Office

UNITED STATES DEPARTMENT OF COMMERCE United States Patent and Trademark Office Address: COMMISSIONER FOR PATENTS P.O. Box 1450 Alexandria, Virginia 22313-1450 www.uspto.gov

DATE MAILED: 05/19/2006

APPLICATION NO.	F	TLING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/806,610	03/23/2004		Toshimitsu Taniguchi	10417-039002 / F51-125462	2451
26211	7590	05/19/2006		EXAMINER	
FISH & RIC	CHARD	SON P.C.	GEBREMARIAM, SAMUEL A		
P.O. BOX 10	22				
MINNEAPOLIS, MN 55440-1022				ART UNIT	PAPER NUMBER
				2811	

Please find below and/or attached an Office communication concerning this application or proceeding.

	Application No.	Applicant(s)	μ
	10/806,610	TANIGUCHI ET AL.	
Office Action Summary	Examiner	Art Unit	
	Samuel A. Gebremariam	2811	
The MAILING DATE of this communication app Period for Reply	ears on the cover sheet with the	correspondence address	•
A SHORTENED STATUTORY PERIOD FOR REPLY WHICHEVER IS LONGER, FROM THE MAILING DA - Extensions of time may be available under the provisions of 37 CFR 1.13 after SIX (6) MONTHS from the mailing date of this communication. - If NO period for reply is specified above, the maximum statutory period w - Failure to reply within the set or extended period for reply will, by statute, Any reply received by the Office later than three months after the mailing earned patent term adjustment. See 37 CFR 1.704(b).	ATE OF THIS COMMUNICATION 16(a). In no event, however, may a reply be ting apply and will expire SIX (6) MONTHS from cause the application to become ABANDON	N. mely filed n the mailing date of this communical ED (35 U.S.C. § 133).	·
Status			
1)	action is non-final. ace except for formal matters, pr		is
Disposition of Claims			
4) ☐ Claim(s) 1.2.4.5 and 22-26 is/are pending in the 4a) Of the above claim(s) is/are withdraw 5) ☐ Claim(s) 22-26 is/are allowed. 6) ☐ Claim(s) 1.2.4 and 5 is/are rejected. 7) ☐ Claim(s) is/are objected to. 8) ☐ Claim(s) are subject to restriction and/or	vn from consideration.		
Application Papers			
9) The specification is objected to by the Examiner 10) The drawing(s) filed on is/are: a) access applicant may not request that any objection to the of Replacement drawing sheet(s) including the correction of the output of of the	epted or b) objected to by the drawing(s) be held in abeyance. Se on is required if the drawing(s) is ob	ee 37 CFR 1.85(a). ojected to. See 37 CFR 1.121	(d).
Priority under 35 U.S.C. § 119	•		
12) Acknowledgment is made of a claim for foreign a) All b) Some * c) None of: 1. Certified copies of the priority documents 2. Certified copies of the priority documents 3. Copies of the certified copies of the prioric application from the International Bureau * See the attached detailed Office action for a list of	have been received. have been received in Applicat ity documents have been receiv (PCT Rule 17.2(a)).	ion No ed in this National Stage	
Attachment(s)			
1) Notice of References Cited (PTO-892) 2) Notice of Draftsperson's Patent Drawing Review (PTO-948) 3) Information Disclosure Statement(s) (PTO-1449 or PTO/SB/08) Paper No(s)/Mail Date S. Patent and Trademark Office	4) Interview Summary Paper No(s)/Mail D 5) Notice of Informal I 6) Other:		

Application/Control Number: 10/806,610

Art Unit: 2811

DETAILED ACTION

Page 2

Request for Continued Examination

- 1. A request for continued examination (RCE) under 37 CFR 1.114, including the fee set forth in 37 CFR 1.17(e), was filed in this application after final rejection. Since this application is eligible for continued examination under 37 CFR 1.114, and the fee set forth in 37 CFR 1.17(e) has been timely paid, the finality of the previous Office action has been withdrawn pursuant to 37 CFR 1.114. Applicant's submission filed on 3/6/2006 has been entered. An action on the RCE follows.
 - a. The amendment filed on 3/6/2006 has been entered.

Double Patenting

3. The nonstatutory double patenting rejection is based on a judicially created doctrine grounded in public policy (a policy reflected in the statute) so as to prevent the unjustified or improper timewise extension of the "right to exclude" granted by a patent and to prevent possible harassment by multiple assignees. A nonstatutory obviousness-type double patenting rejection is appropriate where the conflicting claims are not identical, but at least one examined application claim is not patentably distinct from the reference claim(s) because the examined application claim is either anticipated by, or would have been obvious over, the reference claim(s). See, e.g., *In re Berg*, 140 F.3d 1428, 46 USPQ2d 1226 (Fed. Cir. 1998); *In re Goodman*, 11 F.3d 1046, 29 USPQ2d 2010 (Fed. Cir. 1993); *In re Longi*, 759 F.2d 887, 225 USPQ 645 (Fed. Cir. 1985); *In re Van Ornum*, 686 F.2d 937, 214 USPQ 761 (CCPA 1982); *In re Vogel*, 422 F.2d 438, 164 USPQ 619 (CCPA 1970); and *In re Thorington*, 418 F.2d 528, 163 USPQ 644 (CCPA 1969).

A timely filed terminal disclaimer in compliance with 37 CFR 1.321(c) or 1.321(d) may be used to overcome an actual or provisional rejection based on a nonstatutory double patenting ground provided the conflicting application or patent either is shown to be commonly owned with this application, or claims an invention made as a result of activities undertaken within the scope of a joint research agreement.

Effective January 1, 1994, a registered attorney or agent of record may sign a terminal disclaimer. A terminal disclaimer signed by the assignee must fully comply with 37 CFR 3.73(b).

Art Unit: 2811

4. Claims 1-2 and 4-5 are rejected on the ground of nonstatutory obviousness-type double patenting as being unpatentable over claims of U.S. Patent No. 6,635,952 (952) in view of Soderbarg et al., US patent No. 5,844,272. Although the conflicting claims are not identical, they are not patentably distinct from each other because of the following reasons:

Regarding claim 1, claims 1 and 4-5 of US patent No. (952) teaches (col. 6, lines 51-66, col. 7, line 14-col. 8, line 10 and col. 8, lines 18-20) a semiconductor device comprising: high concentration source (heavily-doped) and drain (heavily) layers of a reverse conductive type (conductivity type of the source/drain region is different than the substrate) formed in a semiconductor layer of one conductive type, a gate electrode formed on a channel layer located between the source and drain layers, a body layer of one conductive type and a low concentration drain layer of the reverse conductive type formed between the channel layer and the high concentration drain layer, wherein: the body layer is formed only under the gate electrode.

(952) does not explicitly state that the body is in direct contact with the high concentration source layer.

It is conventional and also taught by Soderbarg (fig. 3) to form a body region (22) in direct contact with a high concentration source region (24) in a structure of forming a semiconductor device for high voltage application.

It would have been obvious to one of ordinary skill in the art at the time the invention was made to form the body region in direct contact with the high concentration

Art Unit: 2811

source region as taught by Soderbarg in order form a transistor structure with improved high breakdown voltage characteristics (col. 2, lines 48-52).

Regarding claim 2, (952) teaches (col. 7, line 13- col. 8, line 10) the entire claimed structure of claim 1 above including the gate electrode is formed on channel layer via a gate oxide film; wherein the high concentration source layer is adjacent to one end of the gate electrode; wherein the high concentration drain layer is formed apart from an other end of the gate electrode; wherein the low concentration drain layer extends from under the gate electrode and surrounds the high concentration drain layer; and wherein the body layer is formed between the high concentration source layer and the high concentration drain layer.

Regarding claim 4, (952) teaches (col. 8, lines 11-15) the entire claimed structure of claim 1 above including the low concentration drain layer is shallow under the gate electrode and deep under the high concentration drain layer.

Regarding claim 5, (952) teaches (col. lines 7-9) the entire claimed structure of claim 1 above including a reverse conductive type layer is formed in a surface portion of the body layer.

Allowance

5. Claims 22-26 are allowed over the prior art of record.

Allowable Subject Matter

6. The following is an examiner's statement of reasons for allowance: The prior art of record does not teach or suggest, singularly or in combination at least the limitation of

"the body layer is in direct contact with the low concentration source and drain layers such that the body layer protrudes from the low concentration source and drain layers in a downward direction" as recited in claim 22 and "the body layer is in direct contact with the low concentration source and drain layers along portions of each side of the body layer, and the body layer extends in a downward direction to a position below bottom most of contact of the body layer with the low concentration source and drain layer" as recited in claim 23.

Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

Response to Arguments

7. Applicant's arguments with respect to claims 1-2, 4-5 have been considered but are most in view of the new ground(s) of rejection.

Conclusion

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Samuel A. Gebremariam whose telephone number is (571)-272-1653. The examiner can normally be reached on 8:00am-4:30pm.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Eddie Lee can be reached on (571) 272-1732. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

Application/Control Number: 10/806,610

Art Unit: 2811

Page 6

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

SAG May 15, 2006

> DOUGLAS W. OWENS PRIMARY EXAMINER

Wongler K. Over